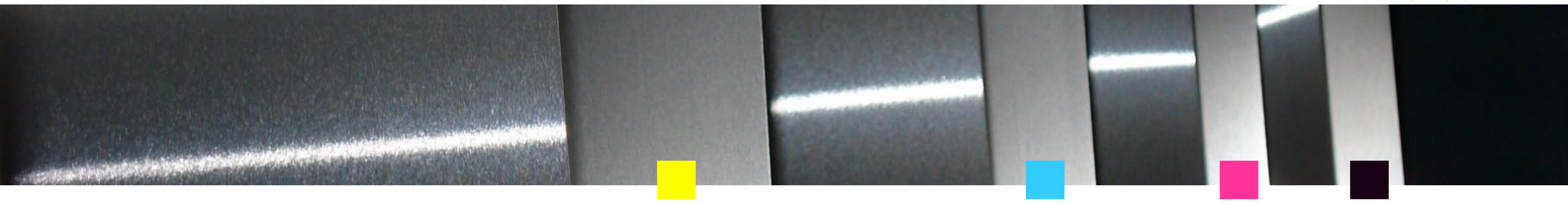
PLATEA D11

DEVELOPER FOR POSITIVE OFFSET PLATES



Developer for Thermal and CTcP-UV positive plates. Direct Use.

PROPERTIES

- ✓ DURABILITY: Its specific formulation permits high productivity under square meters developed.
- ✓ CLEANING: Its dissolution capability reduces the accumulation of emulsion in the filters, rollers and developing tank.
- ✓ COMPATIBILITY: Capable to develop almost all positive Thermal CTP and CTcP UV plates (except closed systems).
- ✓ Non-aggressive to the anodizing layer of the plates.
- ✓ Buffered agents to minimize the aggression to the image area.
- ✓ It contains corrosion inhibitors.
- ✓ Low replenishment rate reduces the consumption and recycling when used with **PLATEA RD1**.

HOW TO USE

Ready to use developer.
Fill the processor machine with developer **PLATEA D11**:

Working temperature:	*General set: 23ºC ± 1ºC (Look for specific setting on plate's TDS)*
Dwell time:	*General set: 30" ± 5" secs (Look for specific setting on plate's TDS)*

Replenisher:

	D11	***RD1***
Replenishment rate	*120 ml/m²*	*50 – 70 ml/m²*
Anti-ox Standby ON	*100 ml/h*	*40 – 60 ml/h*
Anti-ox Standby OFF	*100 ml/h*	*40 – 60 ml/h*

*** These values may vary depending on the conditions and type of the processor.*

SUGGESTIONS

- ✓ Initial bath's charge must be always with developer **PLATEA D11**.
- ✓ Adequate replenishment keeps filters and circulation systems clean prolonging the life of the bath.
- ✓ Correct cleaning of the equipment will avoid contamination of the new bath and prolong the life of the processor. Clean using **LPR-5** and **LP-1**.

PACKAGING

- ✓ 20 litres
- ✓ 200 litres
- ✓ 1000 litres

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